

# BN

## BORON NITRIDE SPUTTERING TARGET

Boron nitride sputtering targets are used for thin film deposition, typically for fuel cell, decoration, electrical insulator, semiconductor, display, LED and photovoltaic devices, glass coating, etc. Boron nitride, with "BN" as its standard chemical symbol, is a ceramic material that has the advantages of high heat capacity, excellent thermal conductivity and low dielectric constant and excellent dielectric strength.

### Features

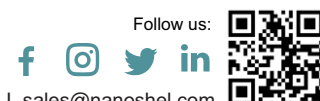
- ✓ High purity
- ✓ Custom Sizes Available

### Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1036	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

### Technical Specification

Molecular Formula	Molecular Weight	Thermal Conductivity
BN	24.82g/mol	26-96 W/m.K



Follow us: [www.nanosHEL.com](http://www.nanosHEL.com) | [sales@nanosHEL.com](mailto:sales@nanosHEL.com)

#### INTELLIGENT MATERIALS PVT LTD

Derabassi  
Punjab (140507)  
INDIA

+91 9779 550077, 9779238252

#### NANOSHEL UK LIMITED

Chapel House,  
Chapel St Cheshire,  
CW12 4AB United Kingdom

+44 (0) 74 105 488, +44 203 137 5187

#### NANOSHEL LLC

3422 Old Capitol Suit  
1305 Wilmington DE - 19808  
United States

+1 646 470 4911

High Purity  
SPUTTERING  
TARGET



20ZICE4589C



19ZAZGO1274G



20ZICE4588M

ISO 9001:2015  
CERTIFIED COMPANY